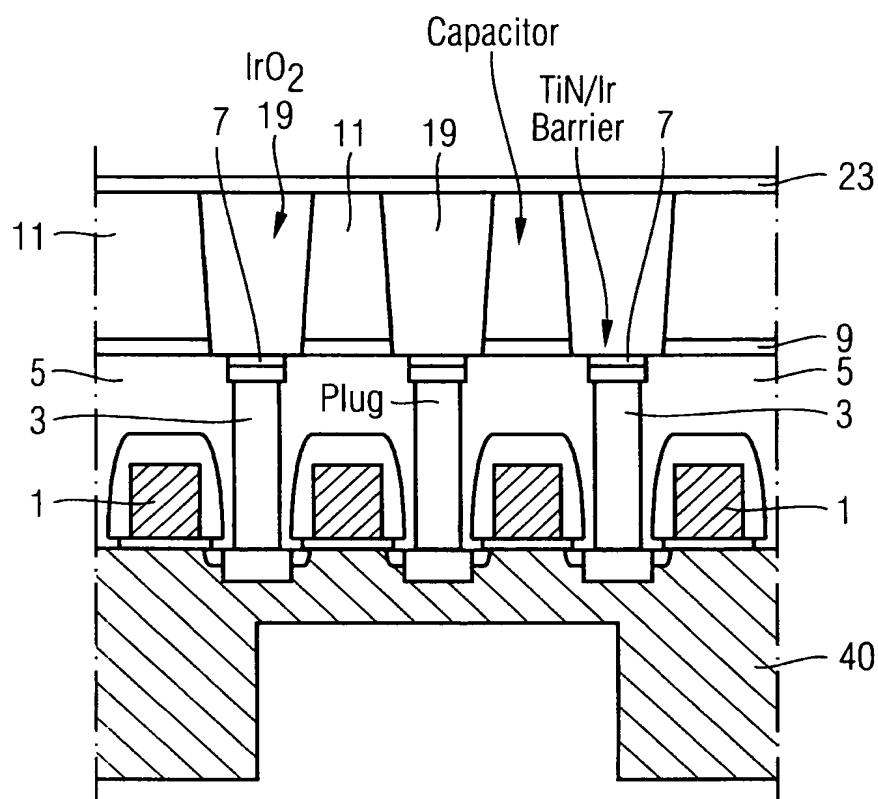




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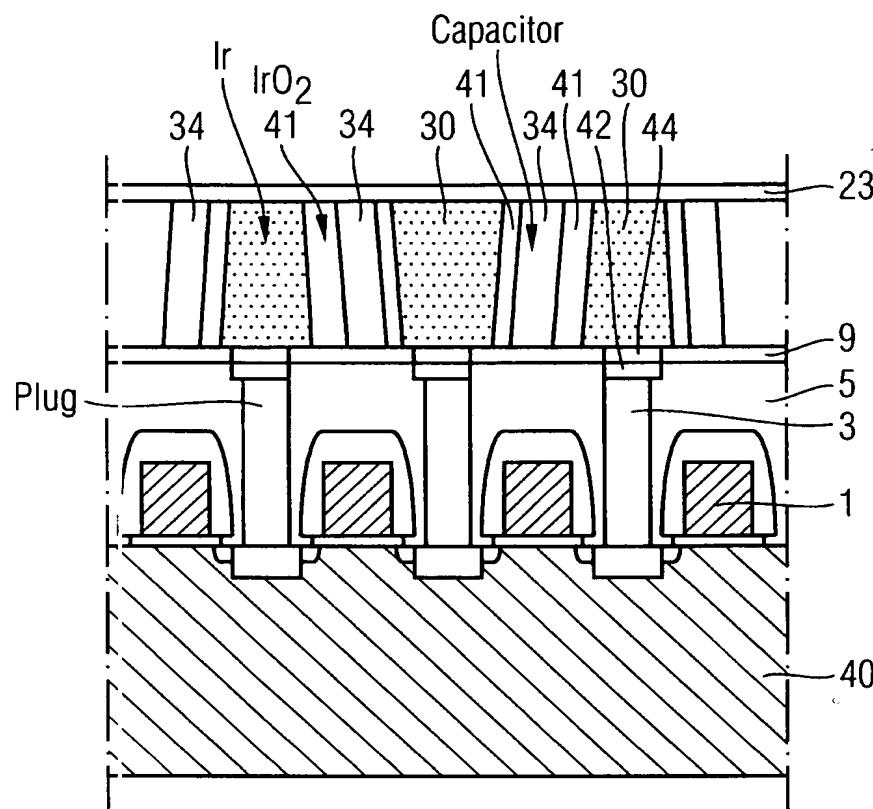
FIG 1
Prior Art





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FIG 2

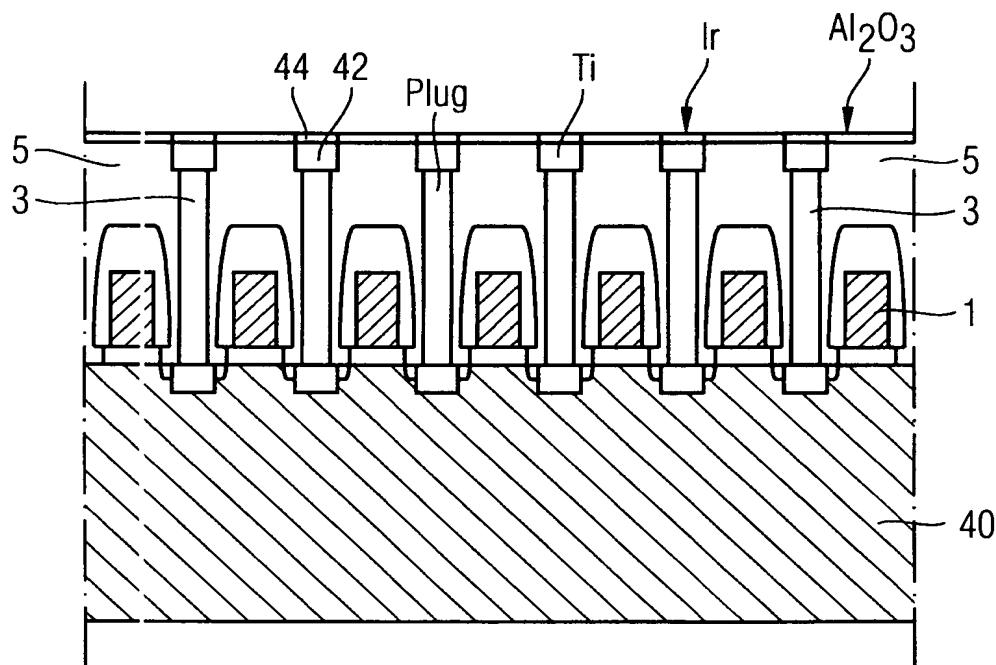




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FIG 3

Before Capacitor Process

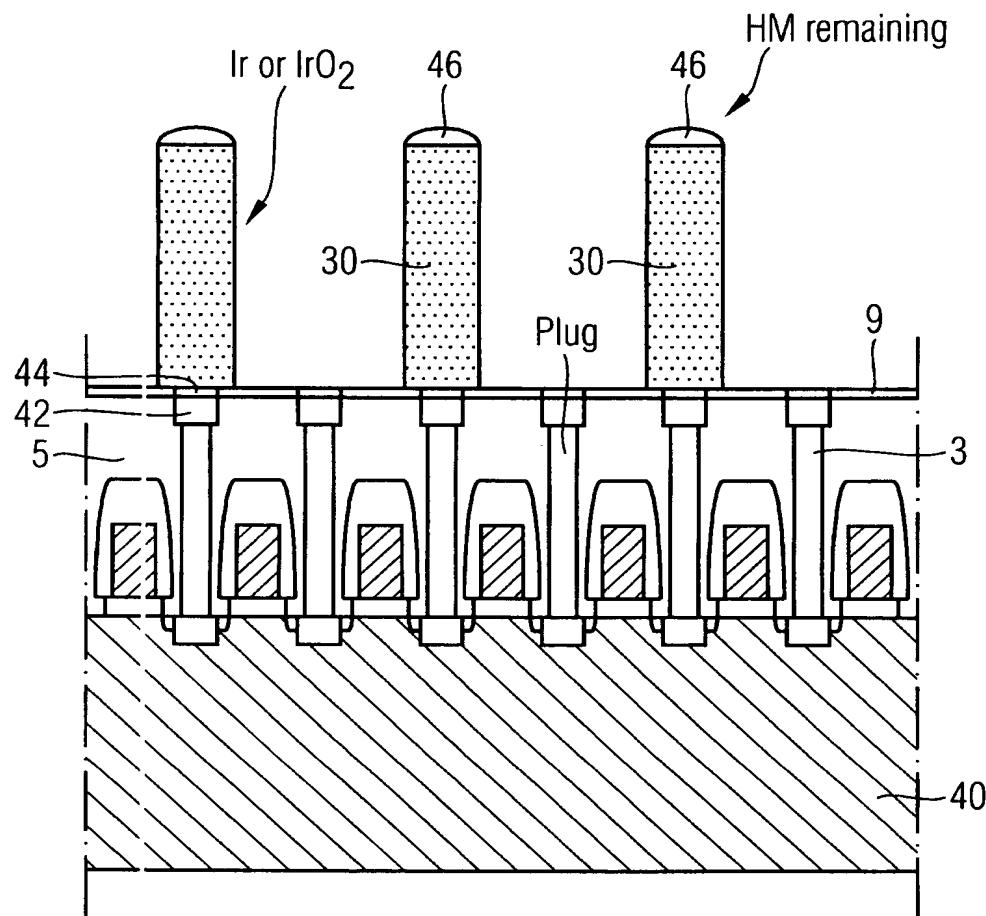




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FIG 4

Ir or IrO₂ Deposit and RIE

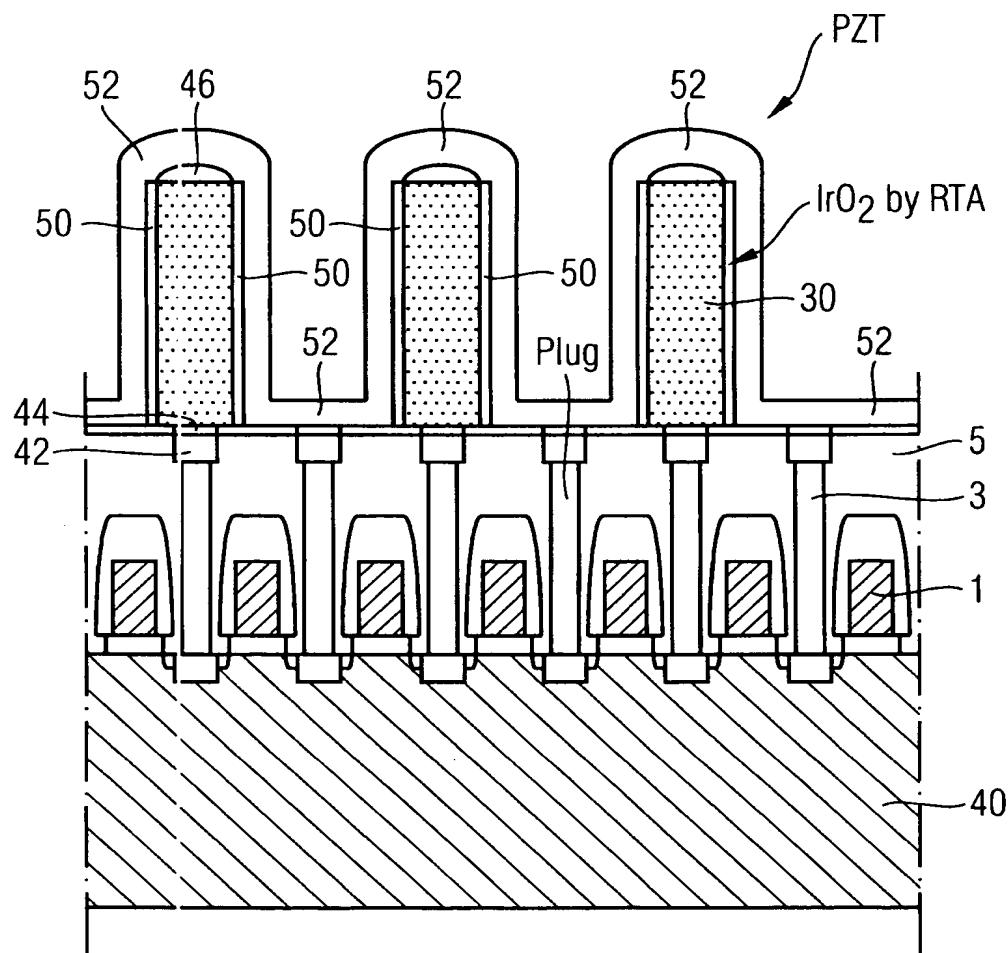




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FIG 5

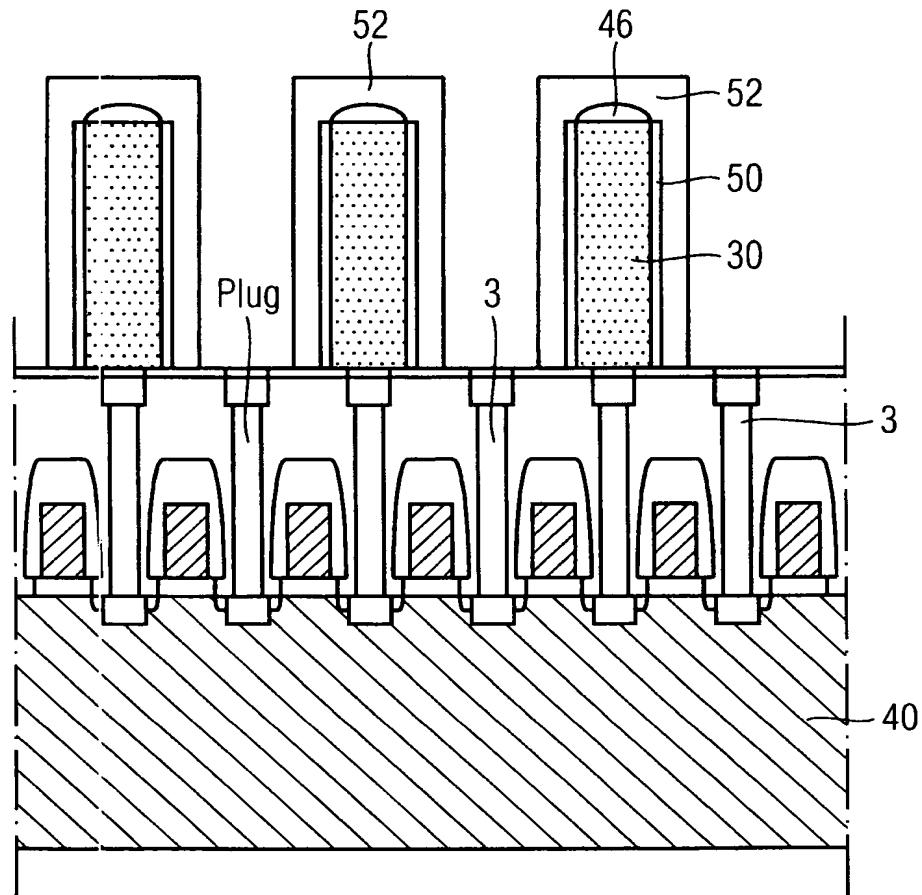
Making IrO_2 on Ir surface
(by RTA, if electrode is IrO_2 , RTA is not necessary)
and PZT Deposit on Surface





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FIG 6
PZT Etch Back





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FIG 7

Fill IrO_2 and Fill Ir
(Or Only fill IrO_2)
CMP and then Al_2O_3 deposit

